

<b>Notice of References Cited</b>	Application/Control No. 10/673,501		Applicant(s)/Patent Under Reexamination MITROVIC, ANDREJ S.	
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*	X	"New approaches for Simulation of Wafer Fabrication: The Use of Control Variates and Calibration Metrics" Chanettre Rasmidatta et al; Proceedings of 2002 Winter Simulation Conference; 2002 - Provided earlier

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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